SHEET 1 OF 2 ORMATION DISCLOSURE ATTY. DOCKET NO. SERIAL NO. 055071-0328 10/756,829 CITATION IN AN APPLICATION **APPLICANT** Robert John SOCHA, et al. FILING DATE **GROUP** (PTO-1449) January 14, 2004 2825 U.S. PATENT DOCUMENTS EXAMINER'S CITE **Document Number Publication Date** Name of Patentee or Applicant of Cited Pages, Columns, Lines, Where INITIALS MM-DD-YYYY Document Relevant Passages or Relevant Number-Kind Code2 (# known) Figures Appear 07/02/2002 Stanton 6,413,684 B1 SM ŲS 6,355,382 B1 03/12/2002 Yasuzato et al. ÜS 5,229,230 07/20/1993 Kamon US 5,895,741 04-20-1999 Hasegawa et al. US 6,214,497 B1 04-10-2001 Stanton US 2002/0152452 A1 10-17-2002 Socha ŪS 5,682,323 10-28-1997 Pasch et al. US 6,303,253 B1 10-16-2001 Lu Wong et al. US 6,223,139 B1 04-24-2001 US 6,777,141 08-2004 Pierrat, Christophe US 6,787,271 09-2004 Cote et al. US 2002/0083410 06-2002 Wu et al. US 6.792.591 09-2004 Shi et al. 02-2003 US 6,519,760 Shi et al. Hau et al. US 2003/0228541 12-2003 US 2002/0157081 10-2002 Shi et al. 10-2004 US 6.807.662 Toublan et al. Adam, Konstantinos 2004/0122636 US 06-2004 FOREIGN PATENT DOCUMENTS Foreign Patent Document Publication Date Pages, Columns, Lines Translation **EXAMINER'S** Name of Patentee or INITIALS Country Codes-Number 4-Kind Applicant of Cited Document Where Relevant MM-DD-YYYY CITE Yes No Figures Appear Codes (if known) OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) **EXAMINER'S** Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, INITIALS journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where CITE published. NO. **EXAMINER** DATE CONSIDERED 01/05/2007 /Suresh Memula/

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